Notice of Allowability	Application No.	Applicant(s)
	10/631,376	BERGMAN, ERIC J.
	Examiner	Art Unit
	Zeinab E. EL-Arini	1792
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIOF the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	plication. If not included will be mailed in due course. THIS
1. This communication is responsive to the revised appeal br	ief filed on 11/15/07.	,
2. X The allowed claim(s) is/are 45-49 and 23 (renumbered 1-6	<u>.</u> L.	
 Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received:	been received. been received in Application No	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requirements
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 		
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.	
(a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) 🔲 hereto or 2) 🔲 to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the O	Office action of
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t		
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 		
	·	
Attachment(s) 1. Notice of References Cited (PTO-892)	5. ☐ Notice of Informal P	atent Application
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☑ Interview Summary	• •
3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	Paper No./Mail Dat 7. 🛛 Examiner's Amendn	e <u>20080119</u> .
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material Of Biological Material	8. ⊠ Examiner's Stateme 9. □ Other Zeinel U	ent of Reasons for Allowance
	ZEINAB EL- PRIMARY EX	

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DETAILED ACTION

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Kenneth Ohriner on 1/18/08.

The application has been amended as follows:

In claim 45, line 8, before "the process", --- " an aqueous form in" --- has been inserted.

In claim 23, line 1, "20" has been changed to read "45".

Claims 20-22, 24, 33-36, 42-44, and 50 have been cancelled.

In the specification, page 1, paragraph 1, line 2, "pending" has been deleted, and ----"U.S. Patent No. 6,869,487"---- has been inserted.

Claims 45-49 and 23 are allowed.

The following is an examiner's statement of reasons for allowance: The prior art of record failed to teach a method of thinning at least one silicon wafer, comprising: placing the wafer into a process chamber; spinning the wafer; spraying a liquid including water onto the spinning wafer, with the liquid forming a substantially uniform liquid layer on the wafer; controlling a thickness of the liquid layer; providing hydrofluoric acid in the process chamber, with the hydrofluoric acid etching a silicon dioxide layer on a surface of the wafer; and providing ozone gas in the process chamber, with the ozone gas oxidizing a silicon surface of the wafer exposed by etching the silicon dioxide layer, and with the HF etching the oxidized silicon surface until the wafer is thinned to approximately 5 to 20% of its initial thickness as claimed.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Zeinab E. EL-Arini whose telephone number is 571-272-1301. The examiner can normally be reached on Monday.-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on 571-272-1414. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Zeinal Elanini Zeinab E EL-Arini Primary Examiner Art Unit 1792

ZEE 1/19/08